

XPY, Acc No: N89-073802

Washing and oxidising semiconductive wafer - by contacting wafer with supercritical carbon dioxide and then with carbon dioxide, etc.

Patent Assignee: HITACHI LTD (HITA)

Number of Countries: 001 Number of Patents: 001

Patent Family:

| Patent No | Kind | Date | Applicat No | Kind | Date | Main IPC | Week |
|------------|------|----------|-------------|------|----------|----------|----------|
| JP 1045131 | A | 19890217 | JP 87201720 | A | 19870814 | | 198913 B |

Priority Applications (No Type Date): JP 87201720 A 19870814

Patent Details:

| Patent | Kind | Lan | Pg | Filing Notes | Application | Patent |
|------------|------|-----|----|--------------|-------------|--------|
| JP 1045131 | A | | 4 | | | |

Abstract (Basic): JP 1045131 A

Semiconductive wafer is brought into contact with supercritical carbon dioxide or liquefied carbon dioxide to be washed, and then semiconductive wafer is brought into contact with carbon dioxide including at least one kind of substance having oxygen, or supercritical carbon dioxide gas similar to carbon dioxide gas, to oxidise Si surface of semiconductive wafer.

Washing and oxidising are performed in one tank. Substance having O is O₂, O₃, H₂O or H₂O₃. Supercritical carbon dioxide gas or liquefied carbon dioxide gas used in washing includes at least one kind of substance having O.

USE/ADVANTAGE - Number of times of contact with air in clean room, of semiconductive wafer can be reduced, so that contamination of wafer by air can be decreased, and yield rate in mfr. of semiconductor, can be improved. Washing and oxidising can be performed in one process, so that mfr. is simplified.

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Title Terms: WASHING; OXIDATION; SEMICONDUCTOR; WAFER; CONTACT; WAFER; SUPERCRITICAL; CARBON; DI; OXIDE; CARBON; DI; OXIDE

Derwent Class: E36; L03; U11

International Patent Class (Additional): B01D-011/04; H01L-021/31

File Segment: CPI; EPI

Manual Codes (CPI/A-N): E31-D02; E31-D03; E31-E; E31-N05C; L04-C09

Manual Codes (EPI/S-X): U11-C04A1; U11-C05B1

Chemical Fragment Codes (M3):

01 C101 C106 C108 C408 C530 C550 C730 C800 C801 C802 C803 C804 C805
C807 C810 M411 M782 M903 M904 M910 Q454 R01066-M R01732-M R01779-M
R01887-M

Derwent Registry Numbers: 1066-U; 1732-U; 1779-U; 1887-U

Specific Compound Numbers: R01066-M; R01732-M; R01779-M; R01887-M

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?t s2/9

2/9/1

DIALOG(R)File 351:DERWENT,WPI

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WPI Acc No: 85-280831/198545

Stripping-off organic coating-hardening films - such as photoresist-film of semiconductor wafers NoAbstract Dwg 0/2

Patent Assignee: HITACHI LTD (HITA)

Number of Countries: 001 Number of Patents: 002

Patent Family:

| Patent No | Kind | Date | Applicat No | Kind | Date | Main IPC | Week |
|-------------|------|----------|-------------|------|----------|----------|----------|
| JP 60192333 | A | 19850930 | JP 8447653 | A | 19840313 | | 198545 B |
| JP 89044013 | B | 19890925 | | | | | 198942 |

Priority Applications (No Type Date): JP 8447653 A 19840313

Patent Details:

| Patent | Kind | Lan | Pg | Filing Notes | Application | Patent |
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| JP 60192333 | A | | 8 | | | |

Title Terms: STRIP; ORGANIC; COATING; HARDEN; FILM; PHOTORESIST; FILM;